A new Si/TiO$_2$/Pt p-n junction semiconductor to demonstrate photoelectrochemical CO$_2$ conversion

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Abstract

This work presents a new Si/TiO$_2$/Pt p-n junction semiconductor prepared by sputtering, chemical vapor deposition (CVD), photolithography and lift-off techniques. XRD, EDS, FE-SEM, diffuse reflectance (DRS) and photocurrent vs potential curves had been used for semiconductor characterization. The material was designed for high porosity and uniformity of both TiO$_2$ and Pt deposits; both TiO$_2$ anatase phase formation and Pt presence were confirmed. This semiconductor has a characteristic of high light absorption in the ultraviolet and visible regions. A good photocurrent response for the cathodic region was obtained in a CO$_2$ saturated solution, confirming electron-hole pair formation and CO$_2$ electron scavenging. A small Si/TiO$_2$/Pt electrode (1 x 1 cm) was employed in photoelectrocatalytic CO$_2$ reduction, forming methanol (0.88 mmol L$^{-1}$), ethanol (2.60 mmol L$^{-1}$) and acetone (0.049 mmol L$^{-1}$) as products. These results had been obtained under the following optimal experimental conditions: 0.1 mol L$^{-1}$ NaHCO$_3$, pH 8 saturated with CO$_2$, 125 W UV-Vis irradiation and -0.8 V bias potential. A Faradaic efficiency of 96.5% was obtained. Suitable charge transfer mechanisms in the electrode surface, and products formation after CO$_2$ reduction, are proposed.

Key words: Si/TiO$_2$/Pt, heterojunction, CO$_2$ reduction, photoelectrocatalysis

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1 Introduction

The conversion of CO$_2$ into value added products and/or high-energy content fuel is one of the major goals in the modern world [1]. Among the various possible approaches, photocatalysis [2–6] and photoelectrocatalysis [7–10] have been demonstrated as promising, mainly because these techniques have advantages over CO$_2$ reduction that can be tuned by using different materials as a photocatalyst when combined with light irradiation. This simple arrangement is able to provide electrons and reactive intermediates able to produce several kinds of hydrocarbons, for instance [11,12]. The photoelectrocatalytic method is based on the use of a semiconductor irradiated by light, whose energy is greater than or equal to that of the band gap, and simultaneously biased by a gradient potential.

Copper and copper oxides [11–19] are the most known widely known p-type semiconductor used for CO$_2$ reduction, but these suffer from a lack of stability. From this some groups have presented the combination of metals and oxides for robust materials. Cheng et al. [20] employed Pt-modified reduced graphene oxide for photoelectrocatalytic CO$_2$ reduction. Yang et al. [21] performed photoelectrocatalytic CO$_2$ reduction using one-dimensional ribbon CoPc enhanced Fe$_2$O$_3$ nanotubes, and Li and coworkers [22] prepared TiO$_2$ nanotubes modified with a CdSeTe nanosheet aiming at photoelectrocatalytic CO$_2$ reduction.

The semiconductor silicon has the interesting properties of mechanical strength, high thermal conductivity, a wide electrical conductivity range and, for the purposes of this work, versatile optical characteristics [23]. However, this material has poor chemical stability and can be easily oxidized in aqueous solution under applied potential [24–27].

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Comment [DW3]: Ref 23 needs a specific page reference to these claims. Otherwise leave it out – most people know this about silicon, anyway.
Nevertheless, the stability and unusual electrocatalytic properties can be obtained with a composite anode based on a TiO$_2$ and Si heterojunction [27,28]. P-n semiconductors heterojunctions have been explored previously as photoactive materials for photocatalytic applications [29,30]. This strategy can usually perform an efficient visible-light absorption and improve charge separation efficiency, leading to photocatalytic activity enhancement. These features demonstrate great potential for photoelectrochemical purposes. In agreement with the literature [25] for a n-Si/n-TiO$_2$ heterojunction, the photogenerated holes under positive bias potential move toward the n-TiO$_2$/electrolyte interface where oxidation reaction takes place. Therefore, the photogenerated electrons in the n-Si move to the counter electrode, where the reduction reaction takes place. For p-Si/n-TiO$_2$ junctions, the flow of electrons and holes at the junction occurs in the opposite direction, generating a smaller photoanodic current density.

Christensen et al [27] has demonstrated that a composite anode based on TiO$_2$ and Si heterojunction coupled to metal grid (n-Si/TiO$_2$/Au) has great potential as a photoanode, where holes generated in the n-Si layer can be accelerated to the surface of the TiO$_2$ by a bias potential. The metal grid combination with a bias potential facilitated the transport of holes from the Si to the TiO$_2$ surface, and the spill over from the TiO$_2$ to the metal grid, culminating in the generation of active chemical species at the semiconductor surface [27]. The semiconductor heterojunction of p-Si/TiO$_2$ has different band bending properties near the junction [25], which enhances the charge separation and minimize recombination within the material. This behavior enhances the possibility of increasing electrons flow at the material semiconductor surface.
Consequently, it could be a good option to promote photoreduction addressed to CO$_2$ conversion for instance.

TiO$_2$ band gap engineering has been reported in the literature for CO$_2$ photocatalytic conversion. TiO$_2$/SiO$_2$ and Ru doped, Pt-TiO$_2$/glass bead and Pt/TiO$_2$ nanotubes supported photocatalysts are reported by Liu and collaborators for CO$_2$ conversion [31]. However, Si/TiO$_2$/Pt photocathode for photoelectrochemical carbon dioxide conversion has not been referenced. Additionally, a small number of materials are described for photoelectrocaytic CO$_2$ reduction.

The present work investigates the development of a novel composite cathode Si/TiO$_2$/Pt p-n junction semiconductor prepared by sputtering, CVD and photolithography techniques and its application on the photoelectrocatalytic CO$_2$ conversion, aiming to generated products with high added value, such as ethanol.

2 Experimental

2.1 Preparation of the new p-n junction Si/TiO$_2$/Pt electrode

The composite p-Si/TiO$_2$/Pt electrodes was obtained by using the following procedures [27]. Firstly, the p-type Si wafer substrate (2.0 inches, university wafers) was carefully cleaned in a H$_2$O$_2$:H$_2$SO$_4$ (1:1) solution during 30 min, washed with deionized water and treated during 2 min in HF:H$_2$O (1:10) solution with the aim of removing the native SiO$_2$ layer from the wafer surface. Afterwards the wafer was rinsed in deionized water, and a TiO$_2$ layer (120 nm) was deposited by sputtering (Moorfield Minilab 3 sputtering system). Argon was used as the sputtering gas, the target was TiO$_2$ and the pressure was maintained at 2 mT during deposition at room temperature.

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The wafer was then annealed at 450 °C for 30 min under N₂ flow. The back contact was composed of a Au/Sb layer (200 nm) alloyed at 400°C for 15 min and a further Au layer (100 nm), both deposited by e-beam evaporation. Two different photoresists (SF9 and SPR350) were spin coated on the TiO₂ surface and baked. The wafer was then placed in a mask aligner for to expose the pattern for the grid electrode. The pattern was developed in a solution of MF319 developer, and the wafer given a further bake. A Ti seed layer (10 nm) was e-beam deposited for better grid adhesion, followed by a 120 nmPt grid layer. The grid was produced by lifting off the photoresist in NMP, followed by final rinsing in acetone, isopropanol and deionized water.

2.2 Characterization of the new p-n junction Si/TiO₂/Pt electrode

The new p-n junction Si/TiO₂/Pt was characterized by X-ray diffraction recorded on a Siemens Model D 5000 diffractometer. The structures and morphologies were analyzed by field emission scanning electron microscopy (FE-SEM) on a Zeiss model Supra 35 equipped with an energy dispersive X-ray (EDX) spectrometer. Diffuse reflectance spectroscopy was performed in both the infrared and visible regions. Linear sweep voltammetry was carried out at 0.01 V s⁻¹ scan rate, in the absence and presence of UV–vis radiation in 0.1 mol L⁻¹ sodium bicarbonate solution as supporting electrolyte, with the supporting electrolyte saturated with CO₂.

2.3 Apparatus and procedure for photoelectrochemical CO₂ reduction

The photoelectrocatalytic CO₂ reduction experiments were performed in a cylindrical two-compartment glass reactor equipped with a cooling system. The sample of p-Si/TiO₂/Pt (1 x 1 cm) was inserted in one compartment of the photoelectrocatalytic
reactor (400 mL) as a working electrode with a saturated Ag/AgCl (KCl sat) electrode as the reference. The working electrode was irradiated by a commercial 125 W UV–Vis light with irradiance of 21 mW cm$^{-2}$ without the bulb vertically inserted in a central quartz bulb. A Pt gauze counter electrode (2 x 2 cm) was inserted in the other photoelectrocatalytic compartment. Controlled-potential electrolysis was carried out using a potentiostat Autolab model PGSTAT 302 under a controlled potential of -0.8 V. The photoelectrocatalytic treatment was carried out for dissolved CO$_2$ gas (OXI-MEDIN) at room temperature in 0.1 mol L$^{-1}$ NaHCO$_3$ as the supporting electrolyte. Aliquots were taken at controlled times and products evaluated.

2.4 Product profiles in photoelectrochemical CO$_2$ reduction

Methanol (CH$_3$OH), ethanol (C$_2$H$_5$OH) and acetone (CH$_3$COCH$_3$) were analyzed by gas chromatography on a Model CG-2010 Schimadzu instrument coupled with a flame ionization detector employing the solid-phase micro-extraction technique (SPME) [11]. For this purpose, a 0.5 mL aliquot of the photoelectrolyzed solution was transferred to a sealed container (1.5 mL) and submitted to a heated bath for 7 min at 65 °C. After this time, the fiber was exposed to the container vapors for 5 min and the vapors injected into the gas chromatograph. The chromatographic column employed was Stabilvax RESTEC 30 m length, 0.25 mm internal diameter and 25 mm film thickness. Nitrogen was used as carrier gas at 1.0 mL min$^{-1}$ flow rate. The injector was maintained at 250 °C and the detector at 260 °C in the splitless mode. The heating ramp used is as follows: 35 °C for 4 min, 45 °C at 2 °C min$^{-1}$, 120 °C at 30 °C min$^{-1}$ and 120 °C for 3 min. Analytical curves were constructed and linear relationship was obtained for acetone in the range of 0.5 µmol L$^{-1}$ to 0.1 mmol L$^{-1}$, with 0.01 to 10.0 mmol

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L⁻¹ for methanol and 0.05 to 7.5 mmol L⁻¹ for ethanol. The determination coefficients and quantification limits were 0.9854 and 0.05 µmol L⁻¹ for acetone, 0.9971 and 0.1 mmol L⁻¹ for methanol, 0.9856 and 0.05 mmol L⁻¹ for ethanol, respectively.

3 Results and discussions

3.1 p-n Si/TiO₂/Pt semiconductor features

Figure 1a illustrates the top view FE-SEM image obtained for the TiO₂/Pt interface of the p-n Si/TiO₂/Pt semiconductor prepared in this study. The presence of Pt and TiO₂ in the semiconductor interface was confirmed by the EDS analysis (Figure 1b). The preparation route led to two different areas, as can be observed in Figure 1a. The left side of the image corresponds to the Pt nanoparticulated area, proven by the EDS results presented in Figure 2b. A FE-SEM image of the main Pt area is shown in Figure 2a. The right area of the Figure 1a image is relative to TiO₂ nanoparticles deposition, which can be confirmed by FE-SEM micrographs and EDS analysis in Figure 3.

Material crystallinity was confirmed by XRD (Figure 4). The diffractogram of the p-n junction Si/TiO₂/Pt semiconductor shows three defined peaks. The peak 2θ = 25⁰ is relative to the TiO₂ anatase phase, the most photoactive phase of this oxide [32]. The peak 2θ = 43⁰ is attributed to Pt, and 2θ = 70⁰ relative to Si. The substrate line in Figure 4 show the peak for Si without modification (2θ = 70⁰) which was suppressed after the TiO₂ and Pt depositions.
3.2 Si/TiO2/Pt behavior under UV-Vis irradiation and effect of CO₂ in the photocurrent/voltage curves

Diffuse reflectance analysis was conducted for a standard Si substrate and for the p-n junction Si/TiO₂/Pt, for evaluation of the semiconductor behavior upon UV-Vis irradiation (Figure 5a). The Si substrate presents high values of optical absorption (dashed curve) in all spectra (200 to 800 nm) mainly in the ultraviolet region. However, deposition of TiO₂ and Pt on the substrate causes an increase in optical absorption in the visible region, with two bands around 400 nm and 500 nm, maintaining higher optical absorption in the ultraviolet regions (≤ 380 nm). This behavior indicates that the material shows excellent optical properties and could absorb light over a wide spectrum.

The inset in Fig. 5(a) shows the Tauc’s graph [33] used to estimate the bandgap energy of the material. The diffuse reflectance measurements were converted to an equivalent absorption coefficient by Kubelka-Munk equation:

\[ \alpha = \frac{(1 - R)^{1/\gamma}}{2R} \]  

(1)

Where \( \alpha \) is the material absorptivity, \( R \) is the reflectance and \( \gamma \) is the power coefficient, which can assume the values 1/2, 3/2, 2 or 3 according to the electronic transition type: direct allowed, direct forbidden, indirect allowed and indirect forbidden, respectively [34,35]. More accurate results in the case of TiO₂ semiconductor are obtained considering the indirect allowed transition (\( \gamma = 2 \)) [36]. The p-n junction Si/TiO₂/Pt revealed a band gap value of 2.75 eV as presented in the inset of Figure 5a. The commonly reported band gap value for TiO₂ anatase is 3.2 eV [37–39]. The difference between the TiO₂ anatase and Si/TiO₂/Pt band gap values can be attributed to doping of the TiO₂ with Pt, which introduces an intragap energy level inside the TiO₂
band gap [40]. This behavior contributes to the absorption threshold of ultraviolet towards visible, in addition to a reduction of the material band gap [40].

Figure 5b shows typical photocurrent vs. potential curves obtained for a Si/TiO$_2$/Pt semiconductor in 0.1 mol L$^{-1}$ NaHCO$_3$ solution in dark conditions (I) and irradiated by UV-Vis light before (II) and after (III) saturation with CO$_2$. A shift towards a less negative potential is observed when the semiconductor is activated by light, indicating that electrons and holes pairs (e$^-$/h$^+$) are created inside both Si and TiO$_2$ due to irradiation in UV-Vis region. The TiO$_2$ is activated by the UV light and visible light can be harvested by the Si [25]. The photogenerated electrons moves toward the Pt/electrolyte interface [27], where water reduction can takes place to generate hydrogen [21,41].

Figure 6 illustrates the process. In the presence of CO$_2$ the curve leads to a larger negative onset potential (from -1 to -0.5 V vs Ag/AgCl), indicating the p-n junction promotes more effective separation of photogenerated charges. This indicates that the flat band potential of the semiconductor is lower than the hydrogen reduction potential and CO$_2$ could be attracted to the Si/TiO$_2$/Pt surface, but requires an external bias potential higher than -0.4 V (Curve III, Figure 5b). This fact indicates that CO$_2$ acts as much better electron scavenger (capturing the photoelectrons generated by e$^-$/h$^+$ separation from Si/TiO$_2$/Pt) than water [22,41]. Si/TiO$_2$/Pt under CO$_2$, light and -0.8 V potential conditions produces a current 5 times higher than the semiconductor without CO$_2$ and light application, and 3 times more intense than under light without CO$_2$ saturation. Based on this results, this condition (-0.8 V) was chosen for
photoelectrocatalytic CO₂ reduction experiments, a potential considerably smaller than the thermodynamic potential (vs NHE) necessary for the CO₂ reduction [42].

The photoactivity results suggested that p-n heterojunction Si/TiO₂/Pt electrode acts as very efficient cathode under negative bias potential. The charge transfer mechanism proposed for Si/TiO₂/Pt p-n heterojunction presented in Figure 6 was proposed based in the research of Hwang and coworkers [25], where the electrons generated by a negative bias potential and light incidence in both surfaces, Si and TiO₂, move to lower energy levels and are consequently trapped by the Pt due to a lower Fermi level. The opposite behavior occurs for holes formed at the semiconductor surface. Therefore, electrons move from the counter electrode towards the working electrode while holes are generated at the photocathode and reach the Pt counter electrode in order to undertake oxidation reactions. Under negative bias, electron/hole pair recombination is minimized by more efficient charge separation, favoring photoelectrocatalysis target [34,43]. The CO₂ reduction occurs at the Pt surface, where it is converted to •CO₂⁻ [6,44–46] and hence protonation and deprotonation reactions occur to form the products [12,47]. The overall charge transfer mechanism characterizes the p-n junction [48].

3.3 Photoelectrochemical CO₂ conversion

The photoelectrocatalytic CO₂ conversion in methanol, ethanol and acetone were monitored during 90 min of photoelectrolysis on a Si/TiO₂/Pt electrode in 0.1 mol L⁻¹ NaHCO₃ saturated with CO₂ (Figure 7a) under a bias potential of -0.80 V and UV-Vis irradiation. The first 30 min of reaction led to the formation of 0.23 mmol L⁻¹ of methanol, 0.72 mmol L⁻¹ of ethanol and 0.025 mmol L⁻¹ of acetone. After 60 min, all the products
formation increased, reaching maximum values at 90 min of reaction with 0.88 mmol L\(^{-1}\) of methanol, 2.60 mmol L\(^{-1}\) of ethanol and 0.049 mmol L\(^{-1}\) of acetone. This is a different result than has been observed in the literature, e.g. [21,22,41,49], where methanol was not generated in the same quantities under these conditions; however, ethanol was, like in our results, the primary product. A faradaic efficiency of 96.5% was obtained after 90 min of photoelectrocatalytic reduction, found by considering the number of electrons necessary for methanol, ethanol and acetone formation by the following reactions:

\[
\text{CO}_2 + 6\text{e}^- + 6\text{H}^+ \rightleftharpoons \text{CH}_3\text{OH} + \text{H}_2\text{O} \quad (1)
\]

\[
\text{CO}_2 + 12\text{e}^- + 12\text{H}^+ \rightleftharpoons \text{C}_2\text{H}_5\text{OH} + \text{H}_2\text{O} \quad (2)
\]

\[
\text{CO}_2 + 16\text{e}^- + 16\text{H}^+ \rightleftharpoons \text{CH}_3\text{COCH}_3 + \text{H}_2\text{O} \quad (3)
\]

The efficiency of photoelectrocatalytic reduction (Si/TiO\(_2\)/Pt, UV-Vis irradiation and -0.80 V) in relation to photocatalysis (Si/TiO\(_2\)/Pt and UV-Vis irradiation) and electrolysis (Si/TiO\(_2\)/Pt and -0.80 V) was compared by monitoring the CO\(_2\) reduction during 90 min in 0.1 mol L\(^{-1}\) NaHCO\(_3\) solution, pH 8, saturated with CO\(_2\), by measuring the formation of methanol, ethanol and acetone. Both experiments were able to form only a small amount of acetone as presented in the insert of the Figure 7b. This comparison confirms CO\(_2\) conversion was more effective under UV-Vis irradiation and bias potential.

The mechanism proposed for methanol, ethanol and acetone formation from photoelectrocatalytic CO\(_2\) reduction applied to a p-n junction Si/TiO\(_2\)/Pt semiconductor is presented in Figure 8. The mechanism is proposed in agreement with the literature [21,42,50,51], and is based on e\(^-\) and H\(^+\) transfer. Latest is generated by water oxidation by the holes at the counter electrode [12,17]. The possible reaction shows two different
pathways; one of them driving to ethanol formation, and the other to acetone. There is probably one preferential pathway in this case, and this fact can explain the dominant formation of ethanol and the small amount of acetone. The methanol could be considered as a sacrificial product that needs to be formed initially for further ethanol or acetone generation.

4 Conclusion

A new and efficient p-n junction Si/TiO₂/Pt semiconductor was constructed based on the heterojunction benefits using lift off and photolithography techniques. The material obtained presents high porosity of both TiO₂ and Pt deposits, in addition to high light absorption in ultraviolet and visible region. Photocurrent vs potential curves showed a characteristic behavior of a p-n junction semiconductor with a good response in the presence of light and CO₂, proving that semiconductor presents highly efficient electron-hole pairs separation and the CO₂ is a more preferential electron scavenger than water. A small Si/TiO₂/Pt electrode (1 cm²) was applied in the CO₂ photoelectrocatalytic reduction, confirming the novel electrode is a promising material for photoelectrochemical reduction purposes. The obtained results showed good performance for methanol (0.88 mmol L⁻¹), ethanol (2.60 mmol L⁻¹) and acetone (0.049 mmol L⁻¹) formation as products, presenting 96% of faradaic efficiency. These results were obtained under the best experimental conditions: 0.1 mol L⁻¹ NaHCO₃, pH 8, saturated with CO₂, 125 W UV-Vis light and -0.8 V. Mechanisms of charge transfer at the electrode surface and for products formation have been proposed in order to clarify how the reactions occur.
5 Acknowledgment

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6 References


Provide Captions

**Figure 1.** (a) FE-SEM image and (b) EDS analysis presenting the interface TiO$_2$-Pt of the Si/TiO$_2$/Pt semiconductor.

**Figure 2.** (a) FE-SEM image and (b) EDS analysis of the Si/TiO$_2$/Pt semiconductor showing the Pt deposit region.

**Figure 3.** (a) FE-SEM image and (b) EDS analysis of the Si/TiO$_2$/Pt semiconductor showing the TiO$_2$ deposit region.

**Figure 4:** XRD diffractogram of the Si/TiO$_2$/Pt semiconductor and the Si substrate.

**Figure 5.** The p-n junction Si/TiO$_2$/Pt (a) diffuse reflectance analysis with an insert of the material band gap and (b) photocurrent vs. potential under dark (line I), under UV-Vis
light (line II) and under UV-Vis light with supporting electrolyte saturated with CO$_2$ (line III).

**Figure 6.** Charge transfer mechanism for the p-n junction Si/TiO$_2$/Pt semiconductor.

**Figure 7.** a) CO$_2$ conversion into the products methanol (CH$_3$OH), ethanol (C$_2$H$_5$OH) and acetone (CH$_3$COCH$_3$) in different times and applying photoelectrocatalysis at -0.8 V and 0.1 mol L$^{-1}$ NaHCO$_3$, pH 8, and b) comparison between the photocatalysis, electrocatalysis and photoelectrocatalysis technique under the same conditions.

**Figure 8.** Mechanism proposed for methanol, ethanol and acetone formation from the photoelectrocatalytic CO$_2$ reduction applied to the p-n junction Si/TiO$_2$/Pt semiconductor.
Figure 5.

Figure 6.
Figure 7.
Figure 8.